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INFORMATION DISCLOSURE 10/623794 TRAD ATEMENT BY APPLICANT **Application Number** July 21, 2003 **Filing Date** Use as many sheets as necessary) Forbes, Leonard **First Named Inventor** 28IT 2823 **Group Art Unit** Unknown Michelle Estrada **Examiner Name** Attorney Docket No: 1303.108US1 Sheet 1 of 11

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STATEMENT BY APPLICANT (Use as many sheets as necessary)	Filing Date	July 21, 2003		
	First Named Inventor	Forbes, Leonard		
	Group Art Unit	2811 2823		
	Examiner Name	Unknown-M: Estrado		
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INFORMATION DISCLOSURE	<b>Application Number</b>	10/623794			
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	First Named Inventor Forbes, Leonard				
	Group Art Unit	2811-2823			
	Examiner Name Unknown M. Estrada				
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	First Named Inventor	Forbes, Leonard		
	Group Art Unit	2811 2823		
,	Examiner Name	Unknown M. Estrada		
Sheet 4 of 11	Attorney Docket No: 1	303.108US1		

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	First Named Inventor	Forbes, Leonard
	Group Art Unit	2811-2823
	Examiner Name	Unknown M. Estrada
Sheet 5 of 11	Attorney Docket No: 1	303.108US1

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Sheet 6 of 11	Attorney Docket No: 1303.108US1		

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ı	Examiner Name	Unknown M. Estrada	
Sheet 7 of 11	Attorney Docket No:	1303.108US1	

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	Group Art Unit	2811 2823	
	Examiner Name	Unknown M. Estrada	
Sheet 8 of 11	Attorney Docket No: 1303.108US1		

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